

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant: Yiming Gu et al.

Practitioner's Docket No.: IDT-1769

Filing Date: 3/25/2004

For: METHOD FOR DETERMINING PHOTORESIST THICKNESS AND STRUCTURE FORMED USING DETERMINED PHOTORESIST THICKNESS

Commissioner for Patent

P.O. Box 1450

Alexandria, VA 22313-1450

Serial No.: 10/808,806

Examiner: Young

Art Unit: 1756

Confirmation No. 7586

**Amendment After Notice of Allowance**

**(37 C.F.R. § 1.312)**

Dear Sir:

Applicants request that the present amendments be entered.

**Amendments to the claims** begin on page 2 of this paper.

**Remarks** begin on page 8 of this paper.